The Laurell 750 Advantage

Choosing your best spin processor



All Laurell Technologies 750 series spin processors come with the following benefits

Custom Hardware and Software: 750 Bluetooth® wireless controller with an all new graphical user interface

Complete Control: Easy programming with advanced features all available at a touch

A Controller that speaks your language: Multiple language options available on one controller

Programming: Time, speed, and acceleration programmed at every step.

Fluid-control process chamber directs materials towards rear drain — no drips encountered when opening chamber

Chemically-resistant clear- view lid with Ø3/4" (Ø19 mm) center opening

Ø1.5" (Ø38 mm) NPP Drain Port

Safety door interlock (disallows rotation when door is open)

Safety door latch (requires deliberate action to open process chamber)

Safety door lock (prevents chamber opening while program is running, or during chuck rotation after program ends)

Vacuum interlock (disallows rotation when there is insufficient vacuum)

Corrosion-proof configuration (no exposed metal — therefore, no degradation using strong acids or bases)

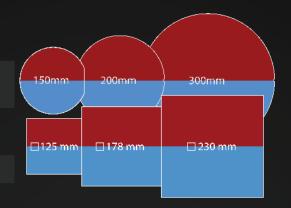
Glovebox-ready configuration (Continuous seal purge with CDA or inert gas required)

Lifetime Process Support

Choose a size that fits your substrate

| | 23 Series | 8 Series | 15 Series |
|--------------------------|-----------|----------|-----------|
| Round substrates up to: | 150 mm/ | 200 mm/ | 300 mm/ |
| | 6 inches | 8 inches | 12 inches |
| Square substrates up to: | 125mm/ | 178 mm/ | 230 mm/ |
| | 5 inches | 7 inches | 9 inches |

The indicated measurements for square substrates are the length of a side









Required facilities





60-70 psig (4-5 bar) of N² or Clean Dry Air



20-28 inches (~504-711mm) Hg. 1.7 - 4.5 SCFM (0.127 M³/min.)

Choose the housing material based on your process and chemistry:

Polypropylene Copolymer

 An exclusive copolymer resistant to solvents, strong acids, and bases

Teflon®

- Widest chemical resistance available
- Required for processing aggressive chemistries such as "Piranha" etch and certain acids at high concentrations

Choose the motor performance that suits your process, now and in the future:

Lz Improved Performance Motor

- Brushless motor suitable for N₂ or Ar environments
- Speed range from 1 to 12,000 RPM
- Acceleration up to 12,000 rpm/second*
- Bi-directional rotation
- Optional homing feature
- Limited lifetime warranty

Hz High Performance Motor

- Brushless motor
- Speed range from 1 to 12,000 RPM
- Acceleration up to 12,000 rpm/second*
- No measurable speed error
- Powerful: Spin larger, heavier substrates
- Bi-directional rotation
- Programmable Agitation
- Limited lifetime warranty

Choose the accessories that will help you achieve your best results:

Dispense Solutions

- **UD-3** center dispense
- **UD-3b** off center dispense and Edge Bead Removal
- **Single Shot Dispense** from an open container
- **Single syringe** manual dispense
- **Multi-syringe** manual dispense

Chucks: Standard and Custom

- Non-vacuum chucks
- Minimum contact chucks
- Fragment chucks
- **Basket processing** chucks
- **CD/DVD** chucks
- **High-Porosity** chucks
- Lens chucks
- Embedded chucks

Other Options

- In-deck, seismic mounting
- Non-wireless connections for secure facilities
- Drain and exhaust options
- Alignment tools

Choose the experts:

Since 1985 **Laurell Technologies** has created a broad range of unique solutions for our customers.

Laurell EDC systems for aqueous processing are custom designed to fit your specific chemistry, process requirements, and ensure your safety

Discuss your needs with our experienced engineers for a complete solution.





Laurell 750 Series systems will be tested for ETL safety certification before the end of 2025 and we will update our certification status when the test results are available



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^{*}Substrate size / weight dependent